What Is Claimed Is:

A method for detecting contaminating species on a wafer edge comprising the steps of:

providing a wafer having contaminating species on an edge portion;

providing a container having a cavity therein for holding a volume of a solvent;

exposing said edge portion of the wafer to said volume of

analyzing said volume of solvent and determining said

exposing said edge portion of the wafer to said volume of solvent; and
analyzing said volume of solvent and determining said contaminating species.

2. A method for detecting contaminating species on a wafer edge according to claim 1 further comprising the steps of:
providing a rotatable shaft having a first end that is 2. A method for detecting contaminating species on a

providing a rotatable shaft having a first end that is free and a second end that is attached to a bearing mounted in a support structure, said support structure having an adjustable height;

mounting said wafer at a center point to said first end of the rotatable shaft;

positioning said wafer vertically in said container and adjusting a height of said bearing such that only a predetermined edge portion of the wafer is exposed to said volume of solvent; and rotating said wafer with said edge portion contacting said volume of solvent by turning said rotatable shaft.

- 3./ A method for detecting contaminating species on a wafer edge according to claim 1 further comprising the step of filling said container with a volume of solvent that comprises an acid.
- 4. A method for detecting contaminating species on a wafer edge according to claim 1 further comprising the step of filling said container with a volume of solvent that comprises HF.
- 5. A method for detecting contaminating species on a wafer edge according to claim 1 further comprising the step of filling said container with a volume of solvent that comprises HF in water at less than 20 vol. %.

- 6. A method for detecting contaminating species on a wafer edge according to claim 1 further comprising the step of exposing an edge portion that is less than 10 mm wide on the wafer to said volume of solvent.
- 7. A method for detecting contaminating species on a wafer edge according to claim 1 further comprising the step of exposing an edge portion that is between about 1 mm and about 3 mm wide on the wafer to said volume of solvent.
- 8. A method for detecting contaminating species on a wafer edge according to claim 1 further comprising the step of analyzing said volume of solvent by an inductively coupled plasma mass spectrometer.
- 9. A method for detecting contaminating species on a wafer edge according to claim 1 further comprising the step of providing said container with an arcuate bottom formed to a radius between about 10 cm and about 15 cm.

- 10. A method for detecting contaminating species on a wafer edge according to claim 2 further comprising the step of mounting said wafer at a center point by vacuum means.
- 11. A method for detecting contaminating species on a wafer edge according to claim 2 further comprising the step of mounting said wafer at a center point by a vacuum suction cup.
- 12. A method for detecting contaminating species on a wafer edge according to claim 2 further comprising the step of rotating said wafer by turning said rotatable shaft by a motor means.
- 13. An apparatus for collecting contaminating species from a wafer edge comprising:
- a container having a cavity therein for holding a volume of a solvent;
- a wafer mounting device for supporting a wafer over said container such that only a predetermined edge portion is exposed to said volume of solvent.

- 14. An apparatus for collecting contaminating species from a wafer edge according to claim 13, wherein said container being provided with an arcuate bottom formed with a radius between about 10 cm and about 15 cm.
- 15. An apparatus for collecting contaminating species from a wafer edge according to claim 13, wherein said volume of solvent comprises an acid.
- 16. An apparatus for collecting contaminating species from a wafer edge according to claim 13, wherein said volume of solvent comprises HF in water at less than 20 vol. %.
- 17. An apparatus for collecting contaminating species from a wafer edge according to claim 13, wherein said predetermined edge portion is less than 10 mm wide.
- 18. An apparatus for collecting contaminating species from a wafer edge according to claim 13, wherein said predetermined edge portion is between about 1 mm and about 3 mm wide.

19. An apparatus for collecting contaminating species from a wafer ledge according to claim 13, wherein said wafer mounting device further comprises:

a rotatable shaft having a free end and a fixed end, said fixed end being rotatable in a bearing that is mounted in a support structure; and

means for rotating said wafer by rotating said rotatable shaft.

20. An apparatus for collecting contaminating species from a wafer edge according to claim 19, wherein said free end of the rotate shaft is further equipped with a vacuum means for attaching to said wafer.